**NexSil™ 85–40 Colloidal Silica**

**PRODUCT DESCRIPTION**

NexSil™ 85–40 is an alkaline dispersion of 40 – 60 nm colloidal silica at a 40% SiO₂ concentration in water. The particles are negatively charged. The product can be used in paper, steel and precision polishing applications where large particle size colloidal silica is required.

NexSil 85–40 is a good choice for sapphire polishing and other specialty wafer polishing applications. NexSil 85–40 provides good balance between removal rate and surface finish. Consult NYACOL® for recommendations on starting conditions.

**TYPICAL PROPERTIES**

- **Appearance:** Light Milky Sol
- **SiO₂ Content, %:** 39 – 41
- **Na₂O Content, %:** 0.05 – 0.2
- **Particle Size, nm:** 40 – 60 by TEM
- **Particle Size, DLS, Z-Average, nm:** 70 – 90
- **Specific Surface Area, m²/g:** 45 – 75
- **pH:** 8.8 – 9.8
- **Viscosity, cPs:** <20
- **Surface Charge:** Negative

**FOR ADDITIONAL INFORMATION OR TO ORDER MATERIAL**

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